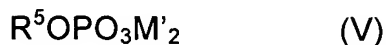
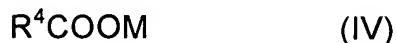
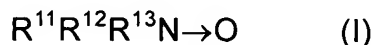


**Complete Set of Claims**

1.[1] (currently amended) A developing solution for use in the development of a photosensitive composition, characterized by comprising a compound, containing at least one hydrophilic group selected from ~~the group consisting~~ of an amine-N-oxide group, a sulfonate group, a sulfate group, a carboxylate group, and a phosphate group, and water.

2.[2] (currently amended) The developing solution according to claim 1, wherein said photosensitive composition comprises a silicon-containing copolymer.

3.[3] (currently amended) The developing solution according to claim 1 ~~or~~ 2, wherein said hydrophilic group-containing compounds are represented by general formulae (I) to (V):



wherein

$R^{11}$ ,  $R^{12}$ ,  $R^{13}$ ,  $R^2$ , and  $R^4$  each independently represent a substituted or unsubstituted alkyl, alkenyl or aryl group;

$R^3$  and  $R^5$  represent a substituted or unsubstituted alkyl, alkenyl, aryl, polyoxyethylene alkyl or polyoxyethylene alkylphenyl group; and

M and M' represent basic group.

4.[4]-(currently amended) The developing solution according to ~~any one of~~ claims 1 ~~to~~ 3, wherein said hydrophilic group-containing compound further comprises at least one group selected from ~~the group consisting of~~ an amine-N-oxide group, a sulfonate group, a sulfate group, a carboxylate group, and a phosphate group.

5.[5] (currently amended) The developing solution according to ~~any one of~~ claims 1 ~~to~~ 4, which further comprises an antifoaming agent.

6.[6] (currently amended) The developing solution according to ~~any one of~~ claims 1 ~~to~~ 5, wherein the content of the compound containing at least one hydrophilic group selected from the group consisting of an amine-N-oxide group, a sulfonate group, a sulfate group, a carboxylate group, and a phosphate group is 0.005 to 2 moles/liter in total.

7.[7] (currently amended) The developing solution according to ~~any one of~~ claims 2 ~~to~~ 6, wherein said silicon-containing copolymer contains a silazane bond.

8.[8] (currently amended) The developing solution according to ~~any one of~~ claims 1 ~~to~~ 7, wherein the temperature is from 20 to 70°C.

9.[9] (currently amended) A method for patterned photosensitive resist film formation, comprising coating a photosensitive composition onto a substrate, exposing the coating, and developing the exposed coating to form a patterned resist film, characterized in that the developing is carried out with a

developing solution comprising a compound, containing at least one hydrophilic group selected from the group consisting of an amine-N-oxide group, a sulfonate group, a sulfate group, a carboxylate group, and a phosphate group, and water.

10.[10] (currently amended) The method for patterned photosensitive resist film formation according to claim 9, wherein the temperature of the developing solution is from 20 to 70°C.

11.(new) The developing solution according to claim 3 where M is selected from an alkali metal, alkaline earth metal and ammonium compound.

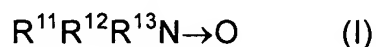
12.(new) The developing solution according to claim 3 where M' is selected from an alkali metal, alkaline earth metal, hydrogen and ammonium compound.

13.(new) The developing solution according to claim 3 where the compound containing at least one hydrophilic group is selected from lauryl dimethylamineoxide, lauryl amidepropylamineoxide, triethylamineoxide,  $O\leftarrow N(CH_3)_2-(CH_2)_{12}-(CH_3)_2N\rightarrow O$ , disodium lauryl sulfosuccinate, sodium dodecylbenzenesulfonate, sodium lauroylsarcosine, sodium laurylsulfate, triethanolamine laurylsulfate, ammonium laurylsulfate, sodium polyoxyethylene alkyl ether sulfates, ammonium laurate, sodium laurate, sodium palmitate, potassium stearate, and ammonium oleate, and salts of acylated amino acids, sodium, potassium, ammonium, triethanolamine salts of alkylphosphoric acids, polyoxyethylene alkyl ether phosphoric acids, and polyoxyethylene alkylphenyl ether phosphoric acids.

14.(new) The method of claim 9, where the photosensitive composition comprises a silicon-containing copolymer.

15.(new) The method of claim 14, where the silicon-containing copolymer contains a silazane bond.

16.(new) The method of claim 9 wherein the hydrophilic group-containing compound is represented by general formulae (I) to (V):



wherein

$R^{11}$ ,  $R^{12}$ ,  $R^{13}$ ,  $R^2$ , and  $R^4$  each independently represent a substituted or unsubstituted alkyl, alkenyl or aryl group;

$R^3$  and  $R^5$  represent a substituted or unsubstituted alkyl, alkenyl, aryl, polyoxyethylene alkyl or polyoxyethylene alkylphenyl group; and

M and M' represent basic group.

17.(new) The method of claim 16, where M is selected from an alkali metal, alkaline earth metal and ammonium compound.

18.(new) The method of claim 16, where M' is selected from an alkali metal, alkaline earth metal, hydrogen and ammonium compound.

19.(new) The method of claim 9, where the compound containing at least one hydrophilic group is selected from lauryl dimethylamineoxide, lauryl amidepropylamineoxide, triethylamineoxide,  $O \leftarrow N(CH_3)_2 - (CH_2)_{12} - (CH_3)_2 N \rightarrow O$ , disodium lauryl sulfosuccinate, sodium dodecylbenzenesulfonate, sodium lauroylsarcosine, sodium laurylsulfate, triethanolamine laurylsulfate, ammonium laurylsulfate, sodium polyoxyethylene alkyl ether sulfates, ammonium laurate, sodium laurate, sodium palmitate, potassium stearate, and ammonium oleate, and salts of acylated amino acids, sodium, potassium, ammonium, triethanolamine salts of alkylphosphoric acids, polyoxyethylene alkyl ether phosphoric acids, and polyoxyethylene alkylphenyl ether phosphoric acids.

20.(new) The method of claim 9, wherein the content of the compound containing at least one hydrophilic group selected from the group consisting of an amine-N-oxide group, a sulfonate group, a sulfate group, a carboxylate group, and a phosphate group is 0.005 to 2 moles/liter in total.